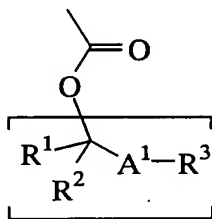


ABSTRACT

A polymer comprising recurring units containing
5 silicon and recurring units having a substituent group of
formula (1) is novel wherein A¹ is a divalent group selected
from furandiyl, tetrahydrofurandiyl and oxanorbornanediyl, R¹
and R² are selected from monovalent C₁-C₁₀ hydrocarbon groups,
or R¹ and R² taken together may form an aliphatic hydrocarbon
10 ring with the carbon atom, and R³ is hydrogen or a monovalent
C₁-C₁₀ hydrocarbon group which may contain a hetero atom. The
polymer is useful as a base resin to formulate a resist
composition which is sensitive to high-energy radiation, and
has excellent sensitivity and resolution at a wavelength of
15 less than 300 nm as well as satisfactory oxygen plasma
etching resistance.



(1)